

Form PTO 1449 U.S. Department of Commerce Patent and Trademark Office Information Disclosure Statement by Applicant	ATTY. DOCKET NUMBER HITA.0120	SERIAL NUMBER 09/987,914
	APPLICANT OSHIMA et al.	
	FILING DATE November 16, 2001	GROUP 2814 2823

U.S. Patent Documents

Examiner Initial	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBC CLASS	FILING DATE

Foreign Patent Documents

Examiner Initial	DOCUMENT NUMBER	FILING DATE	COUNTRY	CLAS S	SUB- CLASS	TRANSLATION	
						YES	NO
QNB	8-316209	5/22/95	Japan	H01L	21/3068	Abstract	X
QNB	9-306988	4/11/96	Japan	H01L	21/768	Abstract	X

Other Documents (Including Author, Title, Date Pertinent Pages, Etc.)

QNB	"The Etching of Low-l Films - The keys to the application of organic films in Cu damascene structures are resistance to heating and to O ₂ -plasma", Semiconductor World 1998, pp. 74-76 (translation pp. 1-7)
EXAMINER <i>William M. Brewster</i>	DATE CONSIDERED <i>31 MAR 03</i>
EXAMINER: Initial if citation is considered, whether or not citation is in conformance with MPEP 609; draw a line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant	